L Number	Hits	Search Text	DB	Time stamp
_	2	(("20030003407") or ("20030003683")).PN.	USPAT;	2003/01/25 17:17
			US-PGPUB	2003/01/20 1/11/
_	25384	(resist or photoresist or photopolymer\$7)	USPAT;	2003/01/31 17:10
į		near3 (develop\$3)	US-PGPUB;	2003, 01, 01 1, 110
			EPO; JPO;	
			IBM TDB	
-	1494	((resist or photoresist or photopolymer\$7)	USPAT;	2003/01/31 12:06
		near3 (develop\$3)) with (ultraviolet or	US-PGPUB;	2003,01,31 12.00
		uv)	EPO; JPO;	
			IBM TDB	
_	38757	(Si or silicon or silicone) with (cross	USPAT;	2003/01/31 12:07
		adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	2003/01/31 12:0/
		, , , , , , , , , , , , , , , , , , , ,	EPO; JPO;	
			IBM TDB	
_	58	(((resist or photoresist or	USPAT;	2003/01/31 12:07
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	2003/01/31 12:07
		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or	IBM TDB	
		cur\$3 or harden\$3))	TDH_TDD	
-	391	(ultraviolet or uv) with (neon)	USPAT;	2003/02/15 10:10
		(US-PGPUB;	2003/02/13 10.10
			EPO; JPO;	
			IBM TDB	
_	57	((ultraviolet or uv) with (neon)) and	USPAT;	2002/02/15 10 11
]	((cross adj link\$3 or cur\$3 or harden\$3)		2003/02/15 10:11
		with (polymer\$7 or photopolymer\$7 or	US-PGPUB;	
		photoresist or resist))	EPO; JPO;	
	2		IBM_TDB	
	2	(((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3)	USPAT;	2004/01/09 16:54
		((Closs adj link\$3 of cur\$3 or narden\$3)	US-PGPUB;	
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))) and (neon same	IBM_TDB	
i _	203	(flow or flowrate))		
_	203	((ultraviolet or uv) with (neon)) same	USPAT;	2003/02/15 10:12
		(inert or Ar or argon)	US-PGPUB;	
			EPO; JPO;	
	C 1		IBM_TDB	
-	51	((((resist or photoresist or	USPAT;	2003/01/31 15:49
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	
		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or	IBM_TDB	
	1644	cur\$3 or harden\$3))) and etch\$3		
-	1644	(resist or photoresist or photopolymer\$7)	USPAT;	2003/01/31 17:12
		and ((develop\$3) adj20 (ultraviolet or	US-PGPUB;	
		uv))	EPO; JPO;	· .
		(10)	IBM_TDB	ļ
-	84	((Si or silicon or silicone) with (cross	USPAT;	2003/01/31 17:14
		adj link\$3 or cur\$3 or harden\$3)) and	US-PGPUB;	
	ĺ	((resist or photoresist or photopolymer\$7)	EPO; JPO;	
1		and ((develop\$3) adj20 (ultraviolet or	IBM_TDB	
1_	E03	uv)))	<u></u> -	
	583	430/328.ccls.	USPAT;	2003/02/01 14:11
1			US-PGPUB;	
			EPO; JPO;	
_	1.	420/212 422/222	IBM_TDB	
-	16	430/313.cor. and 430/328.cxr.	USPAT;	2004/01/09 16:55
			US-PGPUB;	1
		ı	EPO; JPO;	
	101	/	IBM_TDB	
-	181	(post adj (expos\$ or develop\$4)) adj20	USPAT;	2003/01/31 18:11
	.	(ultraviolet or uv)	US-PGPUB;	
1	}		EPO; JPO;	
			IBM_TDB	
-	49	((post adj (expos\$ or develop\$4)) adj20	USPĀT;	2003/01/31 18:14
		(ultraviolet or uv)) and ((Si or silicon	US-PGPUB;	
		or silicone) with (polymer\$7 or	EPO; JPO;	
		<pre>photopolymer\$7 or photoresist or resist))</pre>	IBM TDB	·

	1 01			
_	21	<pre>(((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist)))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:30
		not ((silicon or Si) near3 (wafer or		
-	15	substrate)) ((((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist)))	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 16:56
		not ((silicon or Si) near3 (wafer or	1DM_1DB	
		substrate))) and etch\$3		
_	9	("4751170" "4931351" "5407786" "5427649" "5486424" "5688723"	USPAT	2003/02/01 10:33
_	567	"5707783" "5877075" "6190837").PN. 430/328.ccls. not 430/313.cor.	HCDAM -	2002/00/01 14 25
	307	430/328.CCIS. NOT 430/313.COI.	USPAT; US-PGPUB; EPO; JPO;	2003/02/01 14:36
			IBM TDB	
_	1	(((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 16:57
		photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	IBM_TDB	
-	12	(430/328.ccls. not 430/313.cor.) and ((Ar	USPAT;	2004/01/09 16:58
		or argon or inert) with (flow or flowrate or rate))	US-PGPUB; EPO; JPO;	
		or race, ,	IBM TDB	
-	11	((430/328.ccls. not 430/313.cor.) and ((Ar	USPĀT;	2003/08/21 14:46
		or argon or inert) same (flow or flowrate	US-PGPUB;	
		or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert)	EPO; JPO;	
		with (flow or flowrate or rate)))	IBM_TDB	
-	1	((430/328.ccls. not 430/313.cor.) and	USPAT;	2004/01/09 16:58
		(((Ar or argon) and (Ne or neon)) same	US-PGPUB;	, , , , , , , , , , , , , , , , , , , ,
		(flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not	EPO; JPO;	
		430/313.cor.) and ((Ar or argon or inert)	IBM_TDB	
		with (flow or flowrate or rate)))		
_	329	((resist or photoresist or photopolymer\$7)	USPAT;	2003/02/01 15:31
		<pre>and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or</pre>	US-PGPUB; EPO; JPO;	
		slm))) not ((430/328.ccls. not	IBM TDB	
		430/313.cor.) and ((Ar or argon or inert)		
<u> </u>	66	with (flow or flowrate or rate)))		
	66	<pre>((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with</pre>	USPAT; US-PGPUB;	2003/02/01 16:50
		(flow or flowrate or rate or sccm or	EPO; JPO;	
		slm))) not ((430/328.ccls. not	IBM_TDB	
		430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))		
_	15	((resist or photoresist or photopolymer\$7)	USPAT;	2004/01/09 16:59
		and (((Ar or argon) and (Ne or neon)) with	US-PGPUB;	2004/01/03 10:39
		(flow or flowrate or rate or sccm or slm))	EPO; JPO;	
		same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert)	IBM_TDB	
		with (flow or flowrate or rate)))		
-	51	(((resist or photoresist or	USPAT;	2004/01/09 16:59
		photopolymer\$7) and (((Ar or argon) and	US-PGPUB;	
		(Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls.	EPO; JPO;	
'		not 430/313.cor.) and ((Ar or argon or	IBM_TDB	
		<pre>inert) with (flow or flowrate or rate))))</pre>		
		not (((resist or photoresist or		
		photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or		
		rate or sccm or slm)) same etch\$3) not		
		((430/328.ccls. not 430/313.cor.) and ((Ar		
		or argon or inert) with (flow or flowrate		
		or rate))))		

		//20/220 cold	T	
	554	((((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or sccm or slm))) same etch\$3) not	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/08/21 15:11
		((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not ((((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or		
		rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and		
		(Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))))		
_	1984	430/313,317.ccls. not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/08/21 15:39
_	1	photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:59
-	1	<pre>(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and neon</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:01
	304	(ultraviolet or uv) with (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/02/15 10:10
_	0	<pre>(((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))</pre>	USPAT; US-PGPUB; ÉPO; JPO; IBM_TDB	2003/08/21 15:45
	83	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/08/21 15:46
	3	<pre>(((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:55
_	1	("6054379").PN.	USPAT; US-PGPUB	2003/02/21 17:30

F				
_	58	(1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1	USPAT;	2003/08/21 15:58
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
	3	photoresist or resist))	IBM_TDB	
-	3	111, 120,001, did 100, 020, ont. did (ecchips	USPAT;	2003/08/21 16:06
		with chamber)	US-PGPUB;	
			EPO; JPO;	
_	142	420/212 217 1	IBM_TDB	
-	143	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	USPAT;	2003/02/22 17:13
		chamber) not (430/328.ccls. not	US-PGPUB;	
		430/313.cor.)	EPO; JPO;	
	101	420 (212 217 221 221 421 422 2	IBM_TDB	
-	101	(0000)	USPAT;	2003/02/22 17:19
		chamber) not (430/328.ccls. not	US-PGPUB;	
		430/313.cor.)	EPO; JPO;	
_	2231	(regist or photographet) some (/w/t	IBM_TDB	0000/00/00
	2231	(resist or photoresist) same ((ultraviolet or uv) with etch\$3)	USPAT;	2003/02/22 17:23
		or uv) with etch55)	US-PGPUB;	
			EPO; JPO;	
_	175	((resist or photoresist) same	IBM_TDB	0000400400
	1/3	((ultraviolet or uv) with etch\$3)) and	USPAT;	2003/02/22 17:22
			US-PGPUB;	
		430/313,317,328.ccls.	EPO; JPO;	
_	17	(resist or photoresist) same ((ultraviolet	IBM TDB	2002/00/02
	. + /	or uv) with etch\$3 near2 chamber)	USPAT;	2003/02/22 17:23
		or av, with etches hearz chamber)	US-PGPUB;	
			EPO; JPO;	
_	4	250/504R-504H.ccls. and (neon or Ne) with	IBM_TDB	0000/00/00
	1	(ultraviolet or uv)	USPAT;	2003/08/21 16:07
_	2	(((ultraviolet or uv) with (neon)) and	US-PGPUB	2004/01/00 17 00
	-	((cross adj link\$3 or cur\$3 or harden\$3)	USPAT;	2004/01/09 17:03
		with (polymer\$7 or photopolymer\$7 or	US-PGPUB;	
		photoresist or resist))) and (neon same	EPO; JPO;	
		(flow or flowrate))	IBM_TDB]
-	21	430/313.cor. and 430/328.cxr.	HCDATT.	2004/01/00 17 04
		1307 313.001. and 4307 320.0XI.	USPAT;	2004/01/09 17:04
			US-PGPUB; EPO; JPO;	
			IBM TDB	
	16	((((post adj (expos\$ or develop\$4)) adj20	USPAT;	2004/01/09 17:06
	_ [(ultraviolet or uv)) and ((Si or silicon	US-PGPUB;	2004/01/09 17:06
		or silicone) with (polymer\$7 or	EPO; JPO;	
		photopolymer\$7 or photoresist or resist)))	IBM TDB	
		not ((silicon or Si) near3 (wafer or	100-100	
		substrate))) and etch\$3		ŀ
-	3	(((ultraviolet or uv) with (neon)) and	USPAT;	2004/01/09 17:07
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	2004/01/03 17.07
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	ĺ
		photoresist or resist))) and ((Ar or argon	IBM TDB	
		or inert) with (flow or flowrate or rate))		İ
-	0	(430/328.ccls. not 430/313.cor.) and ((Ar	USPAT;	2004/01/09 17:08
		or argon or inert) with (flow or flowrate	US-PGPUB;	,,,,,,,,,,
		or rate))	EPO; JPO;	
			IBM TDB	
-	11	((430/328.ccls. not 430/313.cor.) and ((Ar	USPAT;	2004/01/09 17:09
		or argon or inert) same (flow or flowrate	US-PGPUB;	
		or rate))) not ((430/328.ccls. not	EPO; JPO;	
		430/313.cor.) and ((Ar or argon or inert)	IBM TDB	
	i	with (flow or flowrate or rate)))	_	
-	1	((430/328.ccls. not 430/313.cor.) and	USPAT;	2004/01/09 17:10
		(((Ar or argon) and (Ne or neon)) same	US-PGPUB;	
		(flow or flowrate or rate or sccm or	EPO; JPO;	
1		slm))) not ((430/328.ccls. not	IBM_TDB	
		430/313.cor.) and ((Ar or argon or inert)	_	
		with (flow or flowrate or rate)))	ľ	
-	20	((resist or photoresist or photopolymer\$7)	USPAT;	2004/01/09 17:10
		and (((Ar or argon) and (Ne or neon)) with	US-PGPUB;	
1		(flow or flowrate or rate or sccm or slm))	EPO; JPO;	
		same etch\$3) not ((430/328.ccls. not	IBM_TDB	
		430/313.cor.) and ((Ar or argon or inert)		
L	<u> </u>	with (flow or flowrate or rate)))		

r			-,	1
	0	(((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:11
	586	((((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:12
-	377	or argon or inert) with (flow or flowrate or rate))))) 430/313,317.ccls. not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB;	2004/01/09 17:13
_	1	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or	US-PGPOB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:19
-	1	cur\$3 or harden\$3))) and etch\$3) and (Ne) (((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:20
_	0	<pre>cur\$3 or harden\$3))) and etch\$3) and neon (((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:20
_	102	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 17:21

_	4	<pre>(((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:21
_	71	((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 17:22
_	4	photoresist or resist)) 430/313.cor. and 430/328.cxr. and (etch\$3 with chamber)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 17:23
_	4	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 17:23
-	2	<pre>(((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:55
_	25	430/313.cor. and 430/328.cxr.	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 16:55
-	16	<pre>((((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))) and etch\$3</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:57
-	3	<pre>(((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:57
_	14	(430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 16:58
_	2	((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:58
_	23	((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/10 15:59
	76	(((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:59
	1	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) (((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:00

		_		
_	1	(((((resist or photoresist or	USPAT;	2004/01/09 17:01
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	
		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and neon	IBM_TDB	
_	2	(((ultraviolet or uv) with (neon)) and	USPAT;	2004/01/09 17:03
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	2004/01/09 17:03
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	1
		photoresist or resist))) and (neon same	IBM TDB	1
		(flow or flowrate))	1	
_	21	430/313.cor. and 430/328.cxr. not (etch\$3	USPAT;	2004/01/09 17:04
		with chamber)	US-PGPUB;	
			EPO; JPO;	
			IBM_TDB	
-	16	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	USPAT;	2004/01/09 17:06
		(ultraviolet or uv)) and ((Si or silicon	US-PGPUB;	
		or silicone) with (polymer\$7 or	EPO; JPO;	
		photopolymer\$7 or photoresist or resist)))	IBM_TDB	
		not ((silicon or Si) near3 (wafer or substrate))) and etch\$3		
_	3	(((ultraviolet or uv) with (neon)) and	IICDAM.	2004/01/00 17 07
		((cross adj link\$3 or cur\$3 or harden\$3)	USPAT; US-PGPUB;	2004/01/09 17:07
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))) and ((Ar or argon	IBM TDB	
		or inert) with (flow or flowrate or rate))		
-	14	(430/328.ccls. not 430/313.cor.) and ((Ar	USPAT;	2004/01/09 17:08
		or argon or inert) with (flow or flowrate	US-PGPUB;	, , ,
		or rate))	EPO; JPO;	
			IBM_TDB	
-	12	((430/328.ccls. not 430/313.cor.) and ((Ar	USPAT;	2004/01/09 17:09
		or argon or inert) same (flow or flowrate	US-PGPUB;	
		or rate))) not ((430/328.ccls. not	EPO; JPO;	
		430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	IBM_TDB	
_	2	((430/328.ccls. not 430/313.cor.) and	HCDAM.	2004/01/00 17:10
		(((Ar or argon) and (Ne or neon)) same	USPAT; US-PGPUB;	2004/01/09 17:10
		(flow or flowrate or rate or sccm or	EPO; JPO;	
		slm))) not ((430/328.ccls. not	IBM TDB	
		430/313.cor.) and ((Ar or argon or inert)	12100	
		with (flow or flowraté or rate)))		
-	23	((resist or photoresist or photopolymer\$7)	USPAT;	2004/01/09 17:10
		and (((Ar or argon) and (Ne or neon)) with	US-PGPUB;	
		(flow or flowrate or rate or sccm or slm))	EPO; JPO;	
		same etch\$3) not ((430/328.ccls. not	IBM_TDB	
		430/313.cor.) and ((Ar or argon or inert)		
_	76	<pre>with (flow or flowrate or rate))) (((resist or photoresist or</pre>	Haring	0004/04/00 45 45
_	/6		USPAT;	2004/01/09 17:11
		photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or	US-PGPUB; EPO; JPO;	
		rate or sccm or slm))) not ((430/328.ccls.	IBM TDB	•
		not 430/313.cor.) and ((Ar or argon or	1011-100	
j		inert) with (flow or flowrate or rate))))		
İ		not (((resist or photoresist or		
		photopolymer\$7) and (((Ar or argon) and		
		(Ne or neon)) with (flow or flowrate or		
		rate or sccm or slm)) same etch\$3) not		
		((430/328.ccls. not 430/313.cor.) and ((Ar		
		or argon or inert) with (flow or flowrate		
		or rate))))		

-	608	(430/328.ccls. not 430/313.cor.) not (((ultraviolet or uv) with (neon)) and	USPAT;	2004/01/09 17:12
		((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or	US-PGPUB; EPO; JPO;	
		photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or	IBM_TDB	
		rate))) not ((430/328.ccls. not		
		430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not		
		(((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same		
		(flow or flowrate or rate or sccm or		
		slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert)		
		<pre>with (flow or flowrate or rate)))) not (((resist or photoresist or</pre>		
		photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or		
	ļ	rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar		
		or argon or inert) with (flow or flowrate		
		or rate)))) not ((((resist or photoresist or photopolymer\$7) and (((Ar or argon) and		
		(Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls.		
		not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))))		
		not (((resist or photoresist or		
		photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or		
		rate or sccm or slm)) same etch\$3) not $((430/328.ccls. not 430/313.cor.)$ and $((Ar.)$		
		or argon or inert) with (flow or flowrate or rate)))))		
-	1	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with	USPAT; US-PGPUB;	2004/01/09 17:19
		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)	IBM_TDB	
_		(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with	USPAT; US-PGPUB;	2004/01/09 17:20
		(ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or	EPO; JPO; IBM TDB	
_	0	<pre>cur\$3 or harden\$3))) and etch\$3) and neon (((ultraviolet or uv) with (Ne)) and</pre>	-	2004/01/00 17 00
		((cross adj link\$3 or cur\$3 or harden\$3)	USPAT; US-PGPUB;	2004/01/09 17:20
		with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same	EPO; JPO; IBM_TDB	
_	115	(flow or flowrate)) ((ultraviolet or uv) with (Ne)) same	USPAT;	2004/01/09 17:21
		(inert or Ar or argon)	US-PGPUB; EPO; JPO;	
_	5	(((ultraviolet or uv) with (Ne)) and	IBM_TDB	2004/01/00 17 00
		((cross adj link\$3 or cur\$3 or harden\$3)	USPAT; US-PGPUB;	2004/01/09 17:22
		with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon	EPO; JPO; IBM_TDB	
_	74	or inert) with (flow or flowrate or rate)) ((ultraviolet or uv) with (Ne)) and	USPAT;	2004/01/09 17:22
		((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or	US-PGPUB; EPO; JPO;	
_	4	photoresist or resist)) 430/313.cor. and 430/328.cxr. and (etch\$3	IBM_TDB USPAT;	2004/01/00 17 00
		with chamber)	US-PGPUB;	2004/01/09 17:23
		050/50/17 50/17	EPO; JPO; IBM_TDB	
-	4	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv)	USPĀT; US-PGPUB;	2004/01/09 17:23
		·	EPO; JPO; IBM TDB	ĺ
	.1		TDE TDD	

_	17	430/328.ccls. and (uv or ultraviolet or	USPAT:	2004/01/10 17:06
		ultra adj violet) same (temperature or	US-PGPUB;	2004/01/10 17.00
		\$4"degree") same plasma	EPO; JPO;	
			IBM TDB	
-	145	430/328.ccls. and (uv or ultraviolet or	USPAT;	2004/01/10 17:08
		ultra adj violet) same (temperature or	US-PGPUB;	2001/01/10 17:00
		\$4"degree") not plasma	EPO; JPO;	
		-	IBM TDB	
_	41	430/313.ccls. and (uv or ultraviolet or	USPAT;	2004/01/10 16:52
		ultra adj violet) same (\$4"degree") same	US-PGPUB;	
		plasma not 430/328.ccls.	EPO; JPO;	
			IBM TDB	
_	342	(F / Damo (at Of	USPAT;	2004/01/10 19:10
		ultraviolet or ultra adj violet) same	US-PGPUB;	
		(\$4"degree") same plasma	EPO; JPO;	
			IBM TDB	
_	22	The second sing problem and (at or	USPĀT;	2004/01/10 19:15
		ultraviolet or ultra adj violet) same	US-PGPUB;	
		(\$4"degree")	EPO; JPO;	
	<u></u>		IBM_TDB	